Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3345	"349"/\$.ccls. and amorphous adj silicon same semiconductor	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 12:41
L2	960	"349"/\$.ccls. and amorphous adj silicon same (on top overlapping over overlapped overlap) same semiconductor	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 12:41
L3	347	"349"/\$.ccls. and amorphous adj silicon near8 (on top overlapping over overlapped overlap) same semiconductor	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 12:41
L4	230	"349"/\$.ccls. and amorphous adj silicon near8 (on top overlapping over overlapped overlap) near8 semiconductor	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 12:48
L5	8	(("5229644") or ("5822027") or ("5341012")).PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 13:06
L6	9	"257"/\$.ccls. and channel near10 amorphous adj silicon near8 (on top overlapping over overlapped overlap) near8 semiconductor	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/14 12:49
L8	32	"349"/\$.ccls. and (aperture open opening) near9 ratio near10 "80"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/14 13:07

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S1 ,	2	("6515300").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 11:55
S2	2	("6372534").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 15:55
S3 .	4	("5229644").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	OFF	2007/09/13 16:28
S4	2	("5641974").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 12:00
S5	2	("5585951").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 12:19
S6	5	"349"/\$.ccls. and low adj transmittance near8 blue	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 12:24
S7	82	"349"/\$.ccls. and (low lower lowering) near8 transmit\$6 near8 blue	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON .	2007/09/13 12:26

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S10	14	"349"/\$.ccls. and (low lower lowering) near8 transmit\$6 near8 blue same (insulation insulator passivation insulating)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/13 12:29
S11	6	"349"/\$.ccls. and (low lower lowering) near8 transmit\$6 near8 blue.clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/13 12:29
S12	17	(low lower lowering) near8 transmit\$6 near8 blue same (insulation insulator passivation insulating)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2007/09/13 13:09
S13	2	"US 20010002857"	US-PGPUB; USPAT; USOCR; DERWENT	OR	OFF	2007/09/13 15:09
S14	788	"349"/\$.ccls. and (insulator insulation passivation) same (thick thickness) same ("mu.m" "Ang.")	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2007/09/13 15:11
S15	373	"349"/\$.ccls. and (insulator insulation passivation) near8 (thick thickness) near8 ("mu.m" "Ang.")	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2007/09/13 15:17
S16	1161	"349"/\$.ccls. and (insulator insulation passivation insulating) near8 (thick thickness) near8 ("mu.m" "Ang.")	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2007/09/13 15:46
S17	2023	"349"/\$.ccls. and (insulator insulation passivation insulating resin) near8 (thick thickness) near8 ("mu.m" "Ang.")	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2007/09/13 15:18
S18	0	"349"/\$.ccls. and reactive near4 peak near4 wavelength near8 (nanometer nm nano) same (photo near3 resin)	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2007/09/13 15:48
S19	40	"349"/\$.ccls. and wavelength near8 (nanometer nm nano) same (photo near3 resin)	US-PGPUB; USPAT; USOCR; DERWENT	OR.	ON	2007/09/13 15:49

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S20	. 12	"349"/\$.ccls. and (reaction reactive react) same wavelength near8 (nanometer nm nano) same (photo near3 resin)	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON ·	2007/09/13 15:49
S21	23	"349"/\$.ccls. and resin same positive same (methacrylic glycidyl)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:01
S22	919	"349"/\$.ccls. and (methacrylic glycidyl)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:01
S23	53	"349"/\$.ccls. and (methacrylic glycidyl) same resin same (curing cure cured)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:06
S24	12	"349"/\$.ccls. and methacrylic same glycidyl same resin same (curing cure cured)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:08
S25	37	"349"/\$.ccls. and methacrylic same glycidyl same resin	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:15
S26	408	"349"/\$.ccls. and wavelength near10 "365"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:16

S27	397	"349"/\$.ccls. and wavelength near10 "365" near3 (nanometer nm)	US-PGPUB; USPAT;	OR	OFF	2007/09/13 16:16
			USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB			
S28	36	"349"/\$.ccls. and (reaction react reactive reacting) same wavelength near10 "365" near3 (nanometer nm)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:16
S29	39	"349"/\$.ccls. and (reaction react reactive reacting) same wavelength near10 "365" near3 (nanometer nm)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/13 16:17
S30	9	"349"/\$.ccls. and removing adj solution same pixel adj electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:34
S31	382	"349"/\$.ccls. and solution same pixel adj electrode	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/13 16:34